

Supplementary Information

for

**Kinetics and mechanistic investigation into the degradation of naproxen by
UV/chlorine process**

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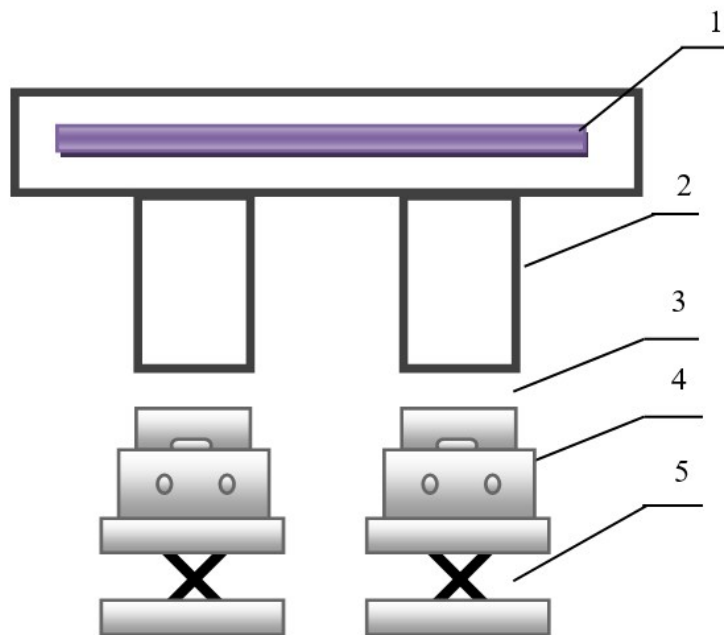


Fig. S1. Schematic description of the reactor

(1. UV lamp; 2. Lampshade; 3. Reaction dish; 4. Magnetic stirrer; 5. Rest pier)

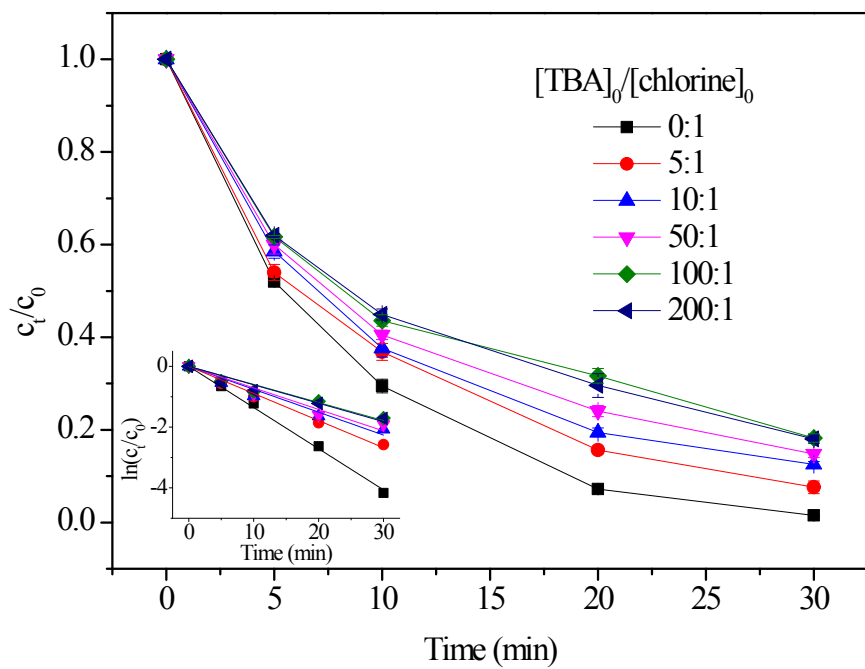
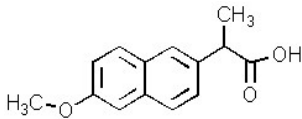
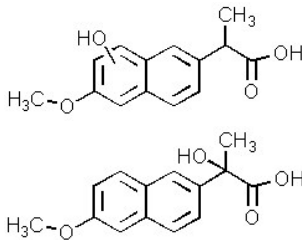
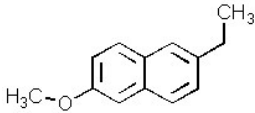
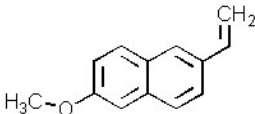
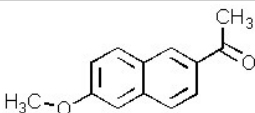
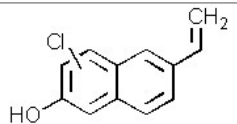
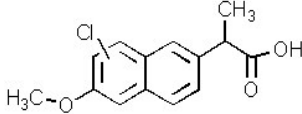
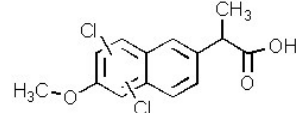
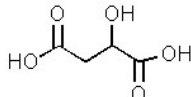
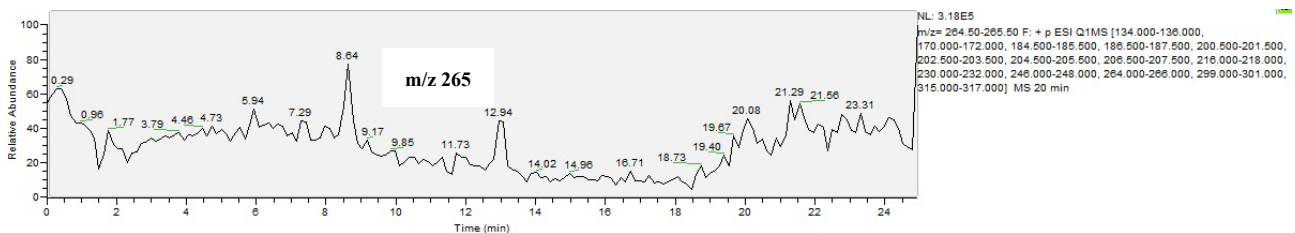
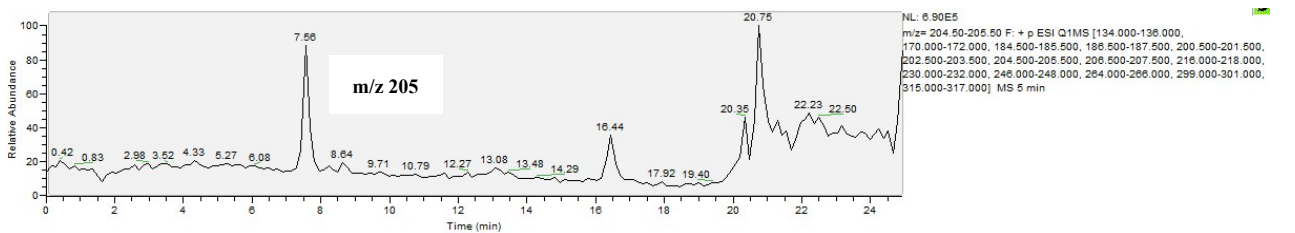
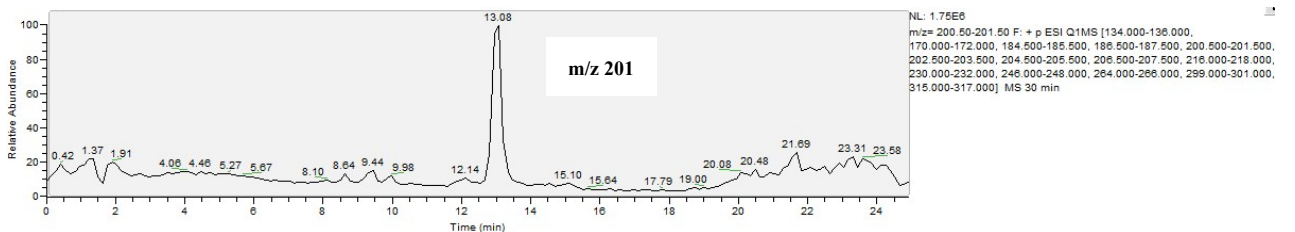
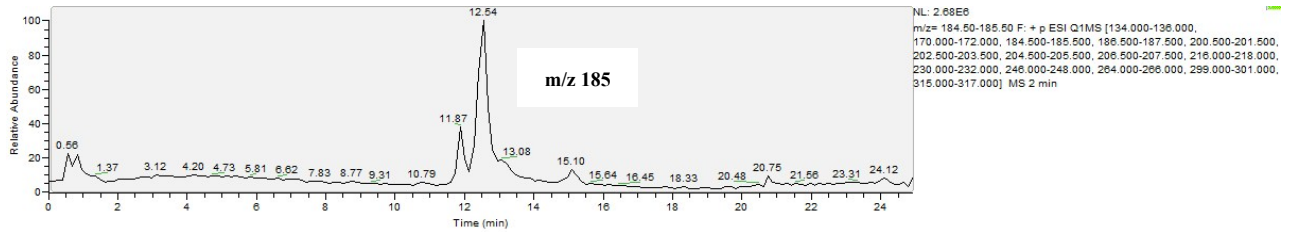
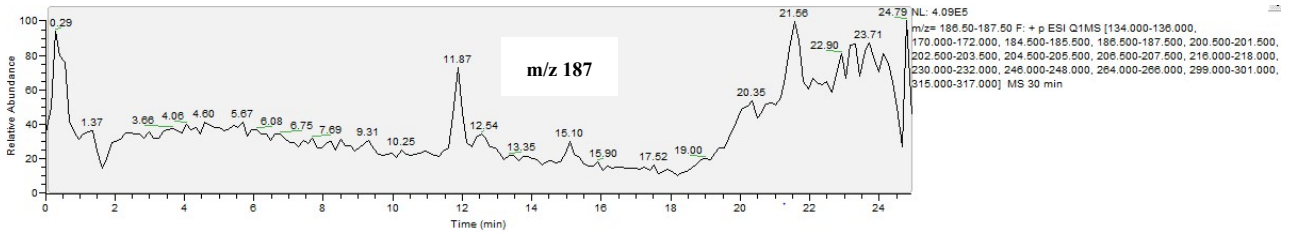
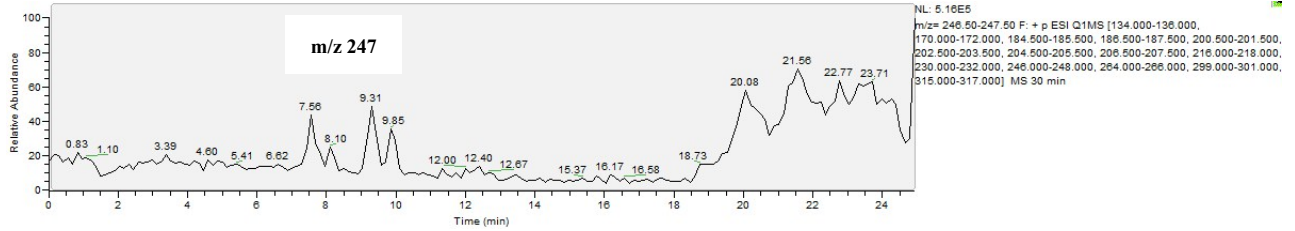
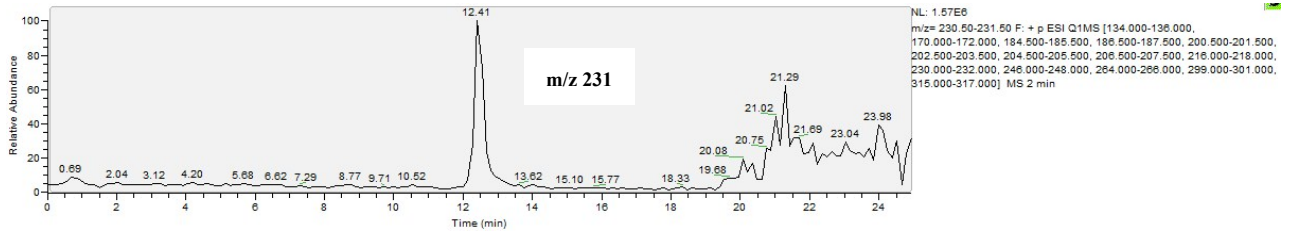


Fig. S2. Effect of different ratios of $[TBA]_0/[NPX]_0$ on NPX degradation by UV/chlorine process

Conditions: $[NPX]_0 = 25 \mu\text{M}$, $[\text{chlorine}]_0 = 250 \mu\text{M}$, $[TBA]_0/[\text{chlorine}]_0 = 0\sim 200:1$,
 $\text{pH} = 7$

Table S1 Identified NPX intermediate products using LC/MS/MS in UV/chlorine process.

Compound	Retention time (min)	m/z	molecular structure
NPX	12.41	231	
P246	7.56, 9.31	247	
P186	11.87	187	
P184	12.54	185	
P200	13.08	201	
P204	7.56	205	
P264	8.64	265	
P299	16.04	300	
P134	1.50	135	



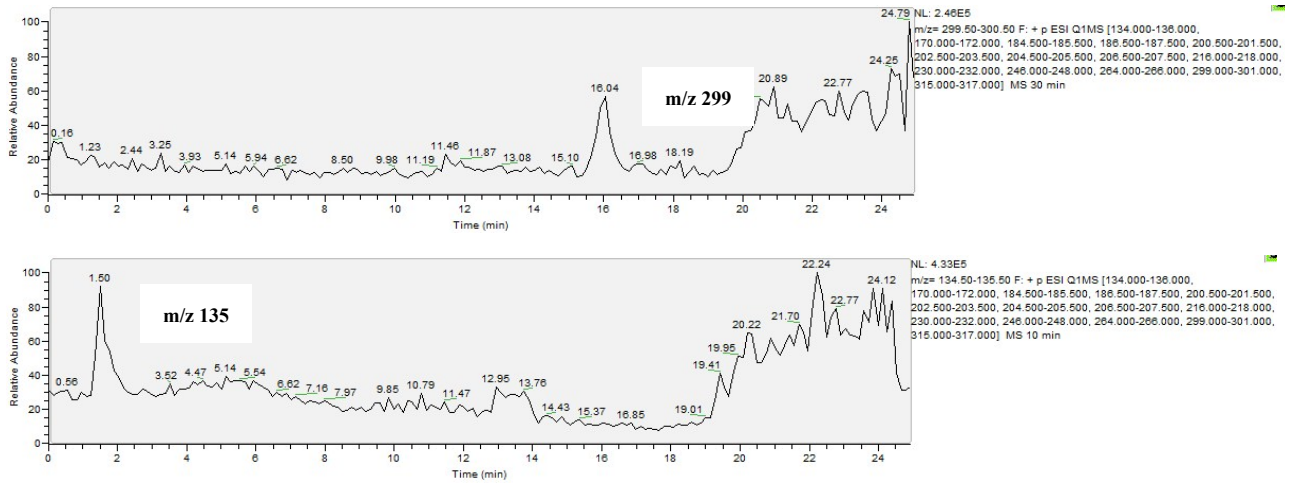
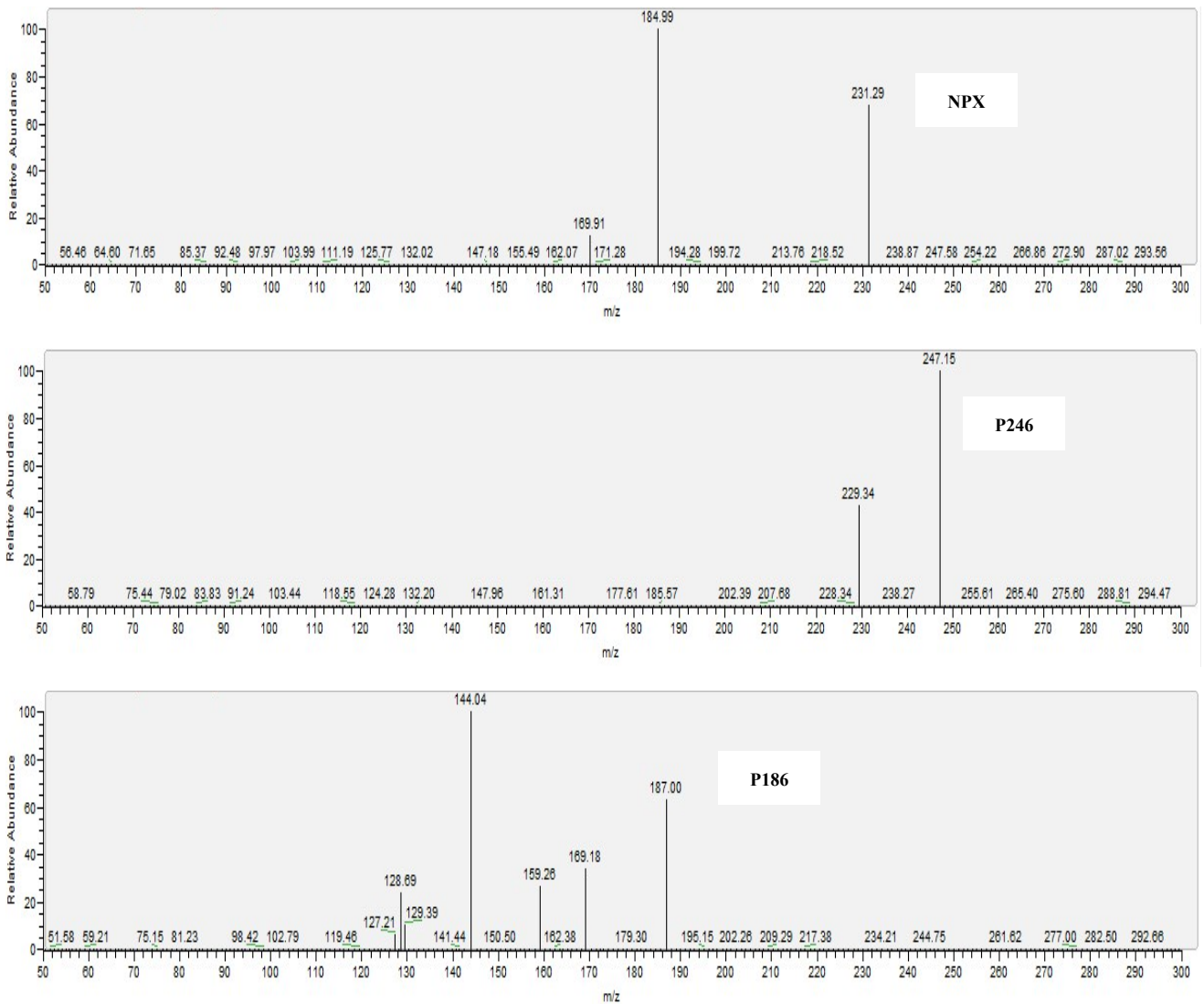
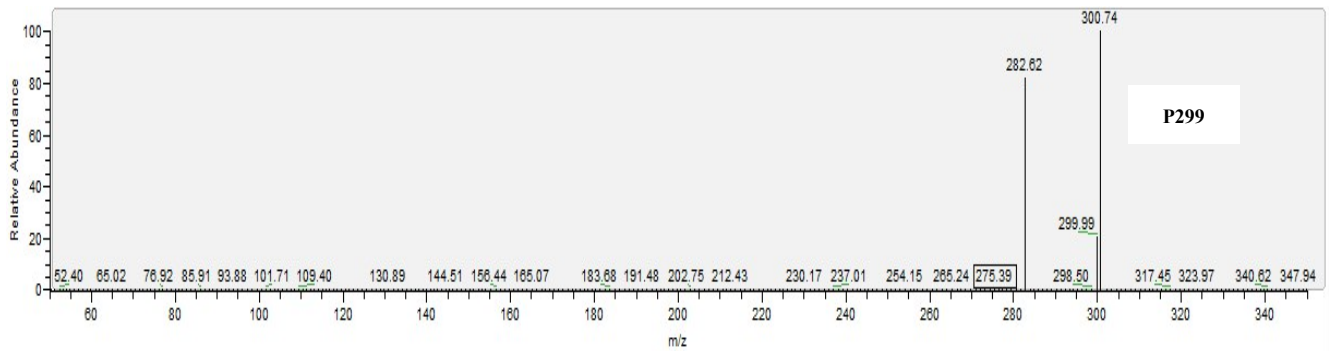
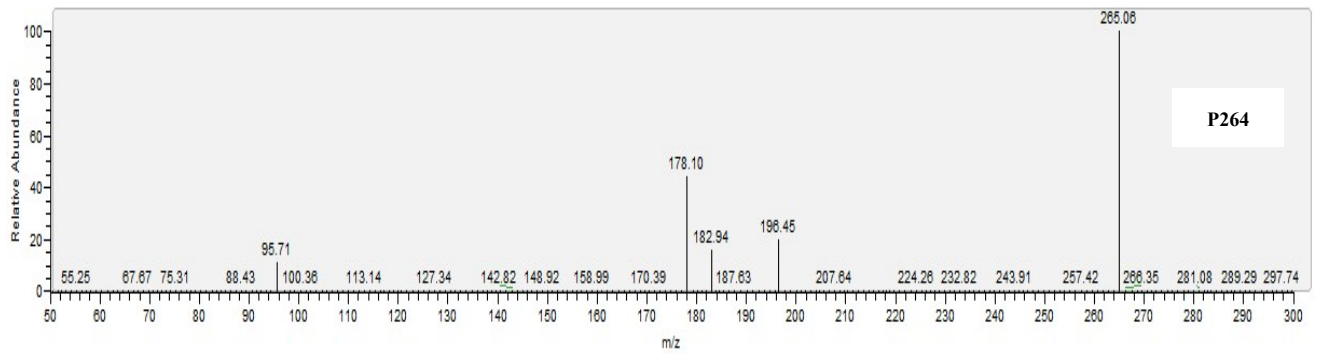
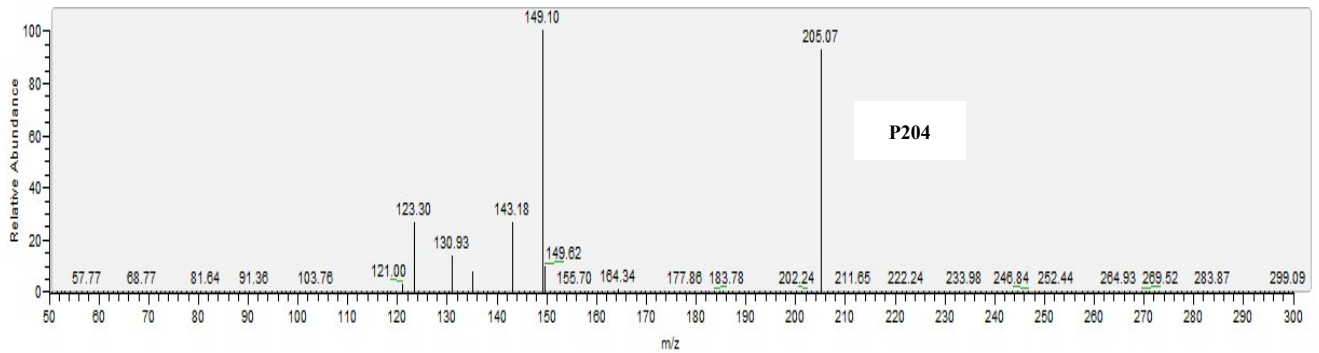
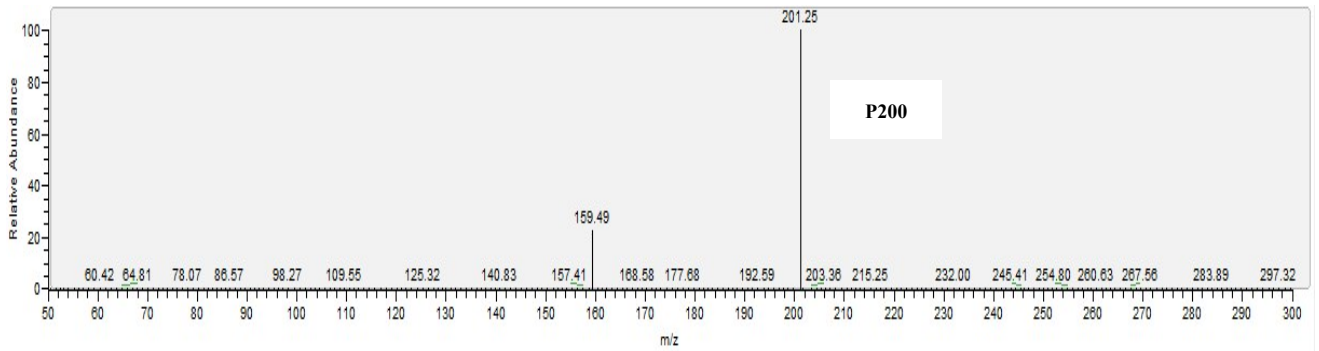
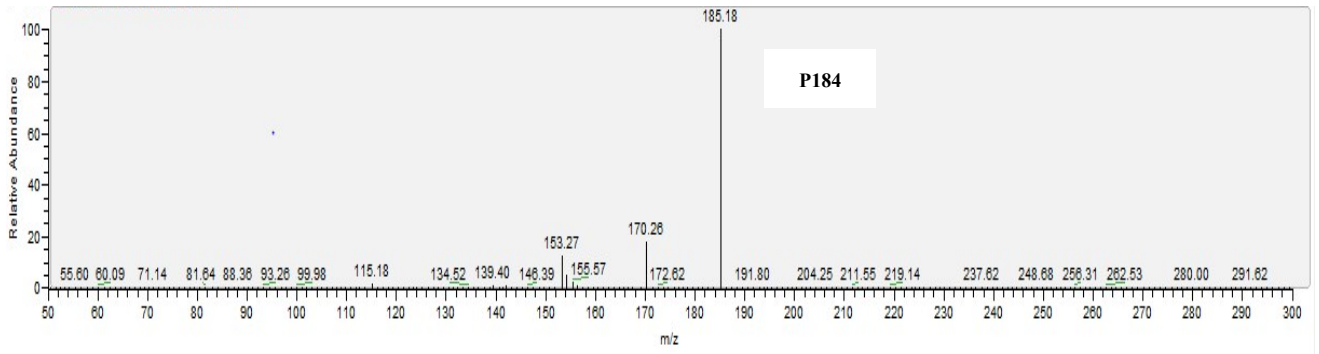


Fig. S3. The LC/MS scan of byproducts of NPX formed during UV/chlorine process by extracting the m/z of ions.





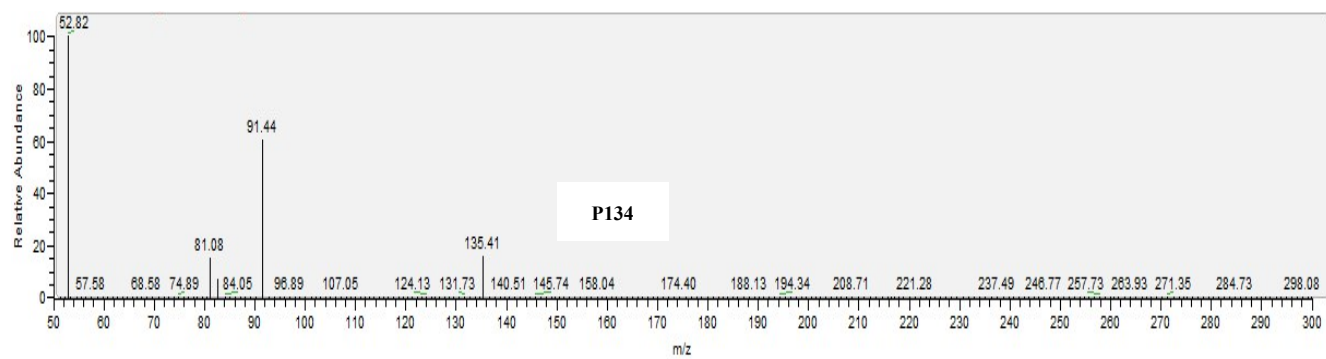


Fig. S4. Mass spectra of NPX and its products.